

## MOCVD Epitaxy and Doping for $\beta$ -Ga<sub>2</sub>O<sub>3</sub> and (Al<sub>x</sub>Ga<sub>1-x</sub>)<sub>2</sub>O<sub>3</sub> (Invited)

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Ultrawide bandgap (UWBG) gallium oxide (Ga<sub>2</sub>O<sub>3</sub>) represents an emerging semiconductor material with excellent chemical and thermal stability. It has a band gap of 4.5-4.9 eV, much higher than that of the GaN (3.4 eV) and 4H-SiC (3.2 eV). The monoclinic  $\beta$ -phase Ga<sub>2</sub>O<sub>3</sub> represents the thermodynamically stable crystal among the known five phases ( $\alpha$ ,  $\beta$ ,  $\gamma$ ,  $\delta$ ,  $\epsilon$ ). The breakdown field of  $\beta$ -Ga<sub>2</sub>O<sub>3</sub> is estimated to be 6-8 MV/cm, which is much larger than that of the 4H-SiC and GaN. These unique properties make  $\beta$ -Ga<sub>2</sub>O<sub>3</sub> a promising candidate for high power electronic device and solar blind photodetector applications. Single crystal  $\beta$ -Ga<sub>2</sub>O<sub>3</sub> substrates can be synthesized by scalable and low cost melting based growth techniques. Metalorganic chemical vapor deposition (MOCVD) growth technique was used to develop high quality  $\beta$ -Ga<sub>2</sub>O<sub>3</sub> thin films and its ternary alloy (Al<sub>x</sub>Ga<sub>1-x</sub>)<sub>2</sub>O<sub>3</sub>. Control of background and n-type doping in  $\beta$ -Ga<sub>2</sub>O<sub>3</sub> will be discussed. Record carrier mobilities of 184 cm<sup>2</sup>/V·s at room temperature and 4984 cm<sup>2</sup>/V·s at low temperature (45 K) were measured for  $\beta$ -Ga<sub>2</sub>O<sub>3</sub> thin films with room-temperature doping concentrations of 2.5×10<sup>16</sup> and 2.75×10<sup>16</sup> cm<sup>-3</sup>, respectively [1]. Growth and fundamental understanding of (Al<sub>x</sub>Ga<sub>1-x</sub>)<sub>2</sub>O<sub>3</sub> are still lacking. The limit of Al incorporation in beta-phase Ga<sub>2</sub>O<sub>3</sub> has not been understood or experimentally verified, although it was predicted up to 60% of Al composition could be incorporated into  $\beta$ -Ga<sub>2</sub>O<sub>3</sub>. N-type doping capability as a function of Al composition in (Al<sub>x</sub>Ga<sub>1-x</sub>)<sub>2</sub>O<sub>3</sub> is another important fundamental question. Carrier transport properties in (Al<sub>x</sub>Ga<sub>1-x</sub>)<sub>2</sub>O<sub>3</sub> will be discussed.

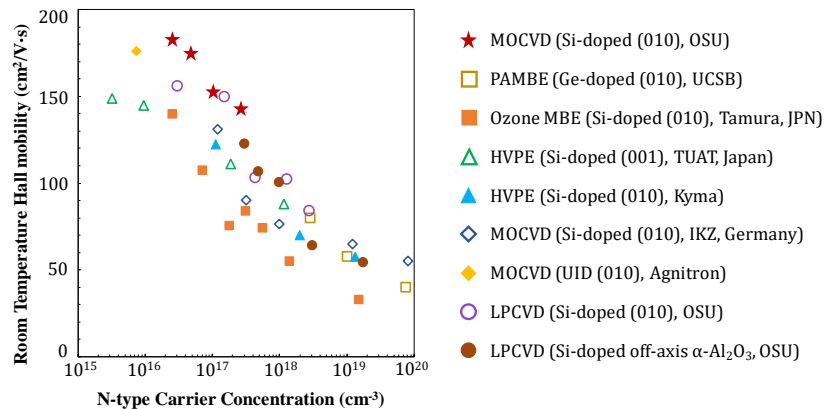


Fig. 1 Results from this work as compared to state-of-the-art: room temperature carrier mobility vs. carrier concentration for (010)  $\beta$ -Ga<sub>2</sub>O<sub>3</sub> films.

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[1] Z. Feng, AFM Bhuiyan, M. R. Karim, H. Zhao, Appl. Phys. Letts, 114, 250601 (2019).